

Ein
TSMC-02-350



April 30, 2004

To: Commissioner for Patents
P.O.Box 1450
Alexandria, VA 22313-1450

Fr: George O. Saile, Reg. No. 19,572
28 Davis Avenue
Poughkeepsie, N.Y. 12603

Subject: | Serial No. 10/757,202 01/14/04 |

Tung-Ching Tseng et al.

METHOD FOR CHEMICAL MECHANICAL
POLISHING OF A SHALLOW TRENCH
ISOLATION STRUCTURE

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

Enclosed is Form PTO-1449, Information Disclosure Citation
In An Application.

The following Patents and/or Publications are submitted to
comply with the duty of disclosure under CFR 1.97-1.99 and
37 CFR 1.56.

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being
deposited with the United States Postal Service as first class
mail in an envelope addressed to: Commissioner for Patents,
P.O. Box 1450, Alexandria, VA 22313-1450, on May 4, 2004.

Stephen B. Ackerman, Reg.# 37761

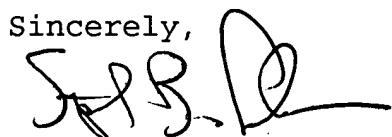
Signature/Date

Spd R D 5/4/04

TSMC-02-350

U.S. Patent Application Publication US 2002/0110995 A1 to Kim, "Use of Discrete Chemical Mechanical Polishing Processes to Form a Trench Isolation Region," discloses a method of forming a trench isolation region using discrete chemical mechanical polishing processes.

Sincerely,



The signature is handwritten in black ink. It consists of stylized initials 'SBA' followed by a surname. The signature is fluid and cursive.

Stephen B. Ackerman,
Reg. No. 37761

Form PTO-1449

INFORMATION DISCLOSURE IN AN APPLICATION

(Use several shovels if necessary)

MAY 06 2004

Doctor Number (Optional)

TSMC-02-350

Laguna Verde

10/757, 202

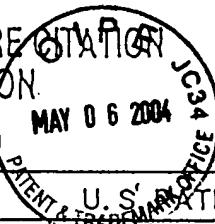
Lecture 1

Tung-Ching Tseng et al.

Expo 00

01/14/04

Raw Materials



U.S. GOVERNMENT

U. S. PATENT DOCUMENTS

FOREIGN PATENT DOCUMENTS

OTHER DOCUMENTS (Including Author, Title, Date, Portion or Pages, Etc.)

- * US Patent Application Publication
 - * US 2002/0110995 A1 to Kim, Pub. Date 08/15/02,
 - * Filed 02/15/01, U.S. Cl. 438/427, "Use of Discrete Chemical Mechanical Polishing Processes to Form a Trench Isolation Region".

Examen

DATE CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.